



Cluster Implants for Advanced Productivity

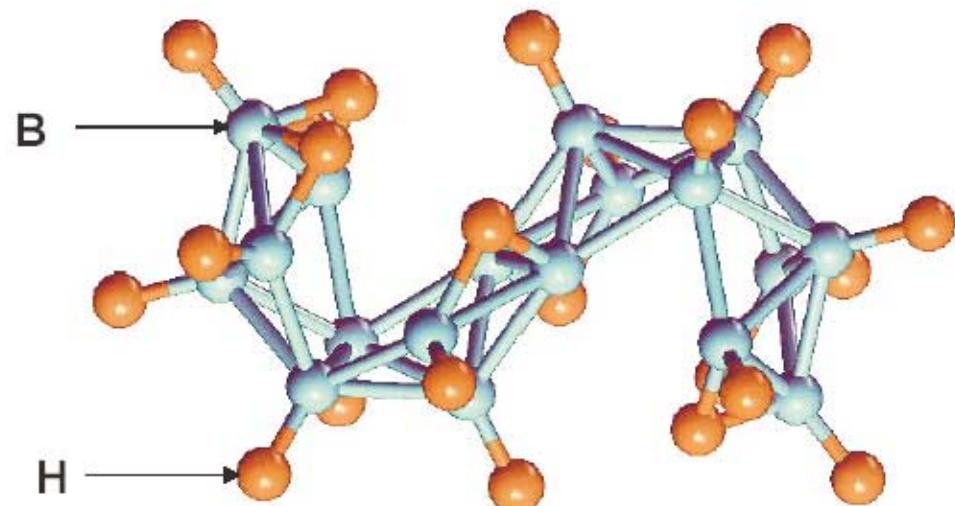
**Dr. Leonard Rubin
Axcelis Technologies**

**Acknowledgements:
Patrick Splinter, Michael Graf**



Cluster Implant Productivity *Outline*

- Productivity Advantages & Challenges of Borane Implantation
- Axcelis History of Borane Implantation
- Machine Design Considerations
- Process Applications, Effects and Results
- Summary





Boron & Borane Compounds

		Mass	Mass/11
■ Boron (B)		11	1
■ Boron Difluoride (BF ₂)		49	~4.5
■ Decaborane (B ₁₀ H ₁₄)		~120	~11
■ Octadecaborane (B ₁₈ H ₂₂)		~210	~19



“Big Borane” $B_{10}H_{14}$ & $B_{18}H_{22}$ **Benefits and Motivation**

- Can dramatically increase ultra-low energy implant throughput
- Implanter can run at much higher extraction energies
- “Drift” operation only thus no energy contamination caused by deceleration
- Same equivalent boron flux can be delivered with much lower electrical beam current
- Low angular divergence



Boranes – Challenges

■ Challenges

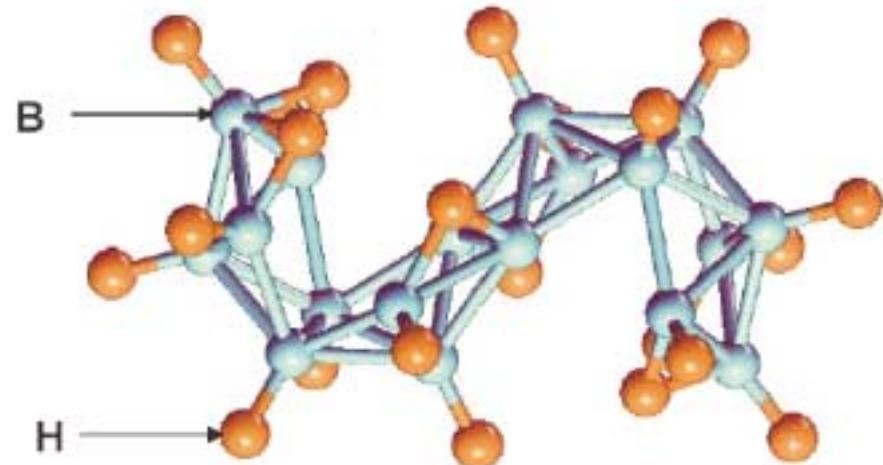
- Machine design considerations
 - Achieving broad application space
 - Design of production capable hardware
- Demonstration of process equivalence



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Decaborane Development History at Axcelis

- Axcelis experimented with decaborane in 1995
 - R&D efforts suspended due to insufficient temperature control in the delivery system.
- Effort restarted in 1999
- Using Decaborane, equivalent beam current on GSD200/E² platform
 - 6.5mA @ 2keV
 - 3.5mA @ 0.5keV
- Source lasted only 10-20 hours before maintenance required
- Production version not completed due to short source life and machine dedication issue

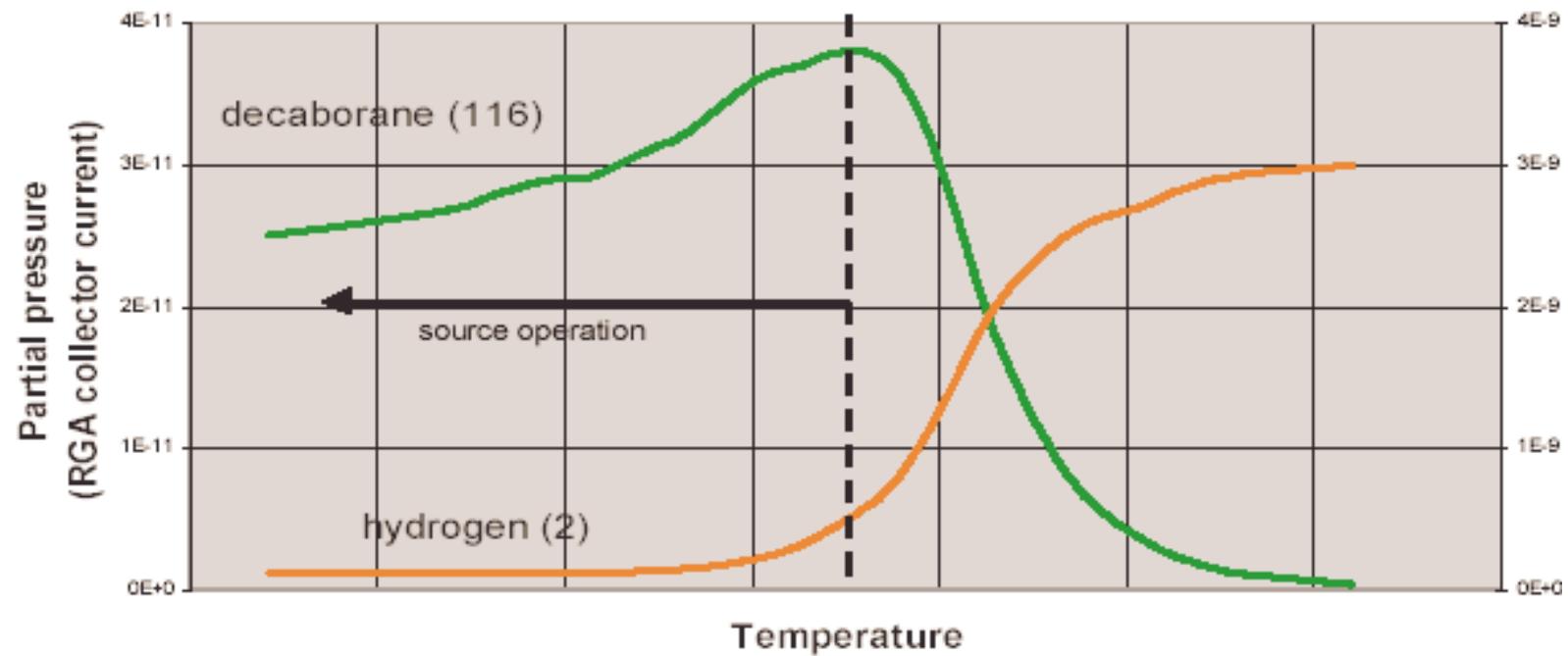




Decaborane Development History at Axcelis *Source Technology – Temperature Control 1999*

- Decaborane production is dependent on arc chamber temperature
- Operating temperature is less than decomposition temperature

Pressure vs. arc chamber temperature





Decaborane Development History at Axcelis Source Technology – Temperature Control 1999

- External temperature control
 - Circulating coolant loop around vaporizer and delivery tube maintains temperature equilibrium

- Internal temperature control
 - Circulating coolant loop through source body limits upper temperature range





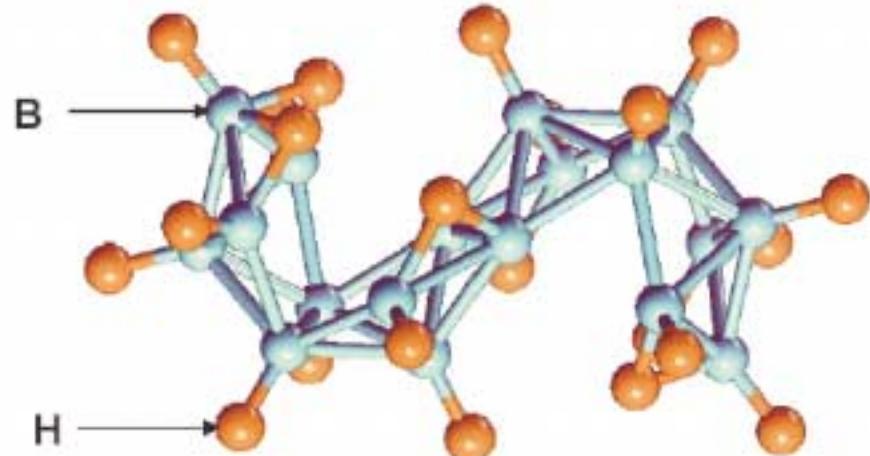
Decaborane Development History at Axcelis 1999-2000 Summary

- Determined temperature range of decaborane decomposition
- Designed and built a temperature-controlled decaborane ion source
- Observed the dimer of decaborane ($B_{20}H_{28}$)
- Oral presentation at IIT 2000



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Analyzer Magnet Design

$$\frac{mv^2}{R} = qvB$$

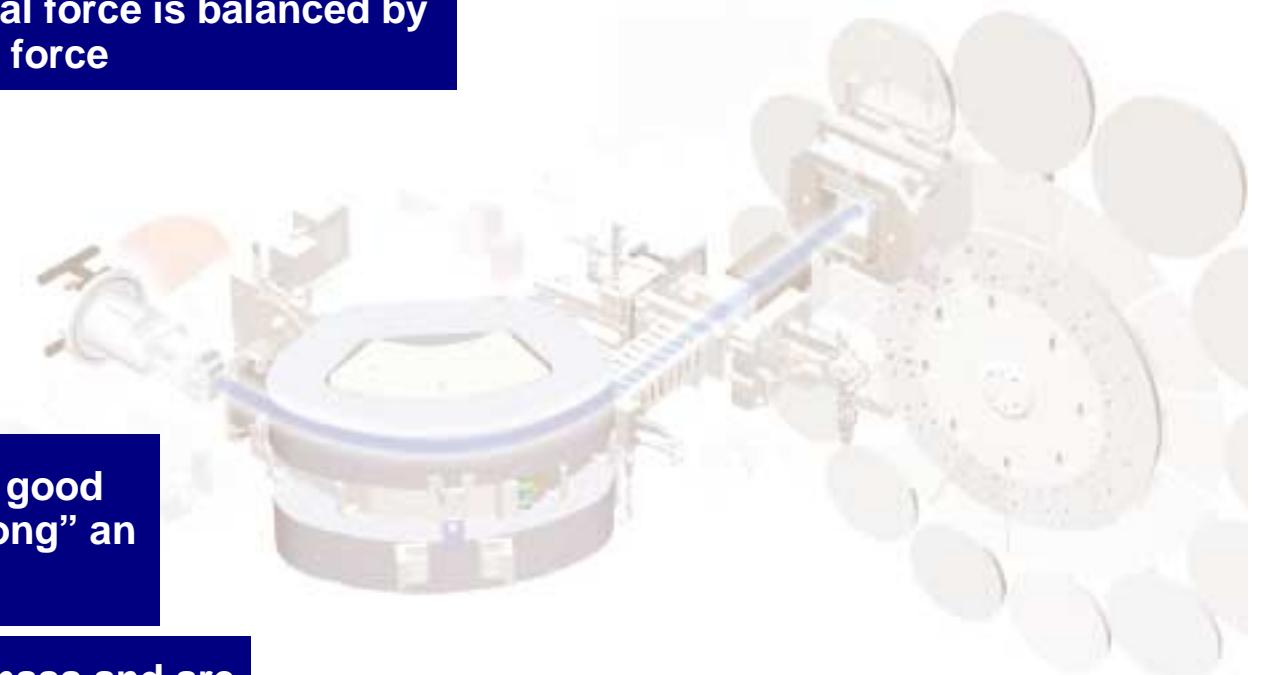


$$\frac{mE}{q} \propto (BR)^2$$

Basic magnet design:
Centripetal force is balanced by magnetic force

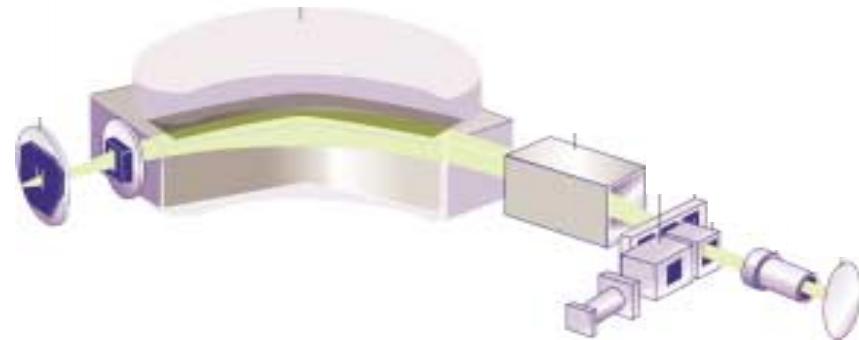
Mass-energy product is a good way to describe how “strong” an analyzer magnet is

Borane ions have higher mass and are transported at higher energy – this is challenging for standard analyzer magnet systems





Transport of B18 *Existing Tool Configurations – Optics Details*

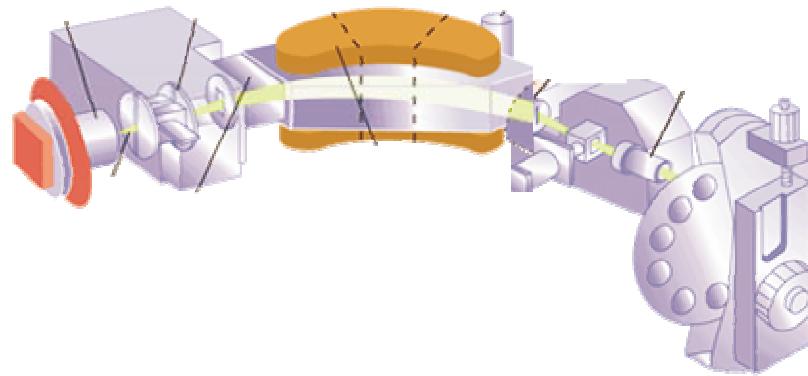


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Tool	Extraction Energy (kV)	Acceleration Energy (kV)	Analyzer Magnet (bend angle, radius)
Ultra	80	None	90°, 30cm
GSD200/E ² -90	90	None	70°, 54cm
GSD200/E ² -180	90	90	70°, 54cm



Transport of B18 *Existing Tool Configurations – Optics Details*

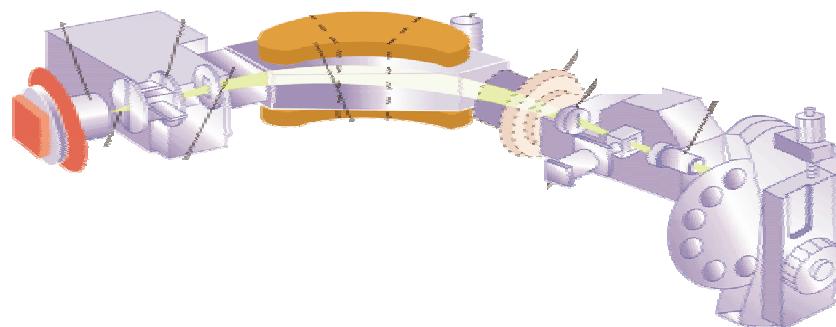


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Maximum Equivalent Boron Energies – B18

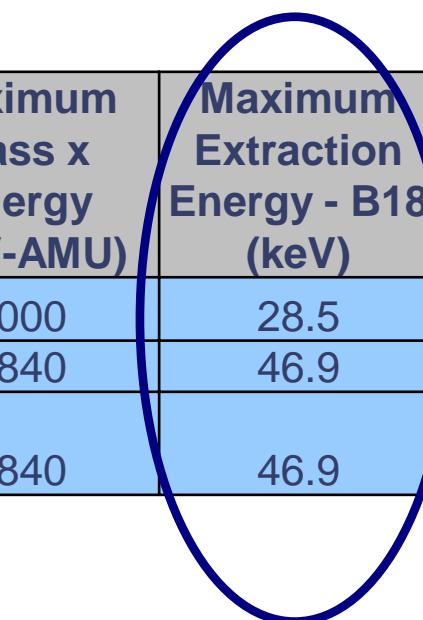
Tool	Maximum Mass x Energy (keV-AMU)	Maximum Extraction Energy - B18 (keV)	Maximum B - Equivalent Extraction (keV)	Maximum B Equivalent Acceleration (keV)	Maximum Total B - Equivalent Energy (keV)
Ultra	6000	28.5	1.5	0.0	1.5
GSD200/E ² -90	9840	46.9	2.5	0.0	2.5
GSD200/E ² -180	9840	46.9	2.5	4.7	7.2

Fixed by Magnet Design
(Radius and Magnetic Field)



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$$= (\text{Mass} * \text{Energy}) / 210$$



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$$= (\text{Max B18 Extraction}) * (11/210)$$



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= (Max Ext) + (Max Accel)



Low Energy Beam Propagation – the effects of space charge

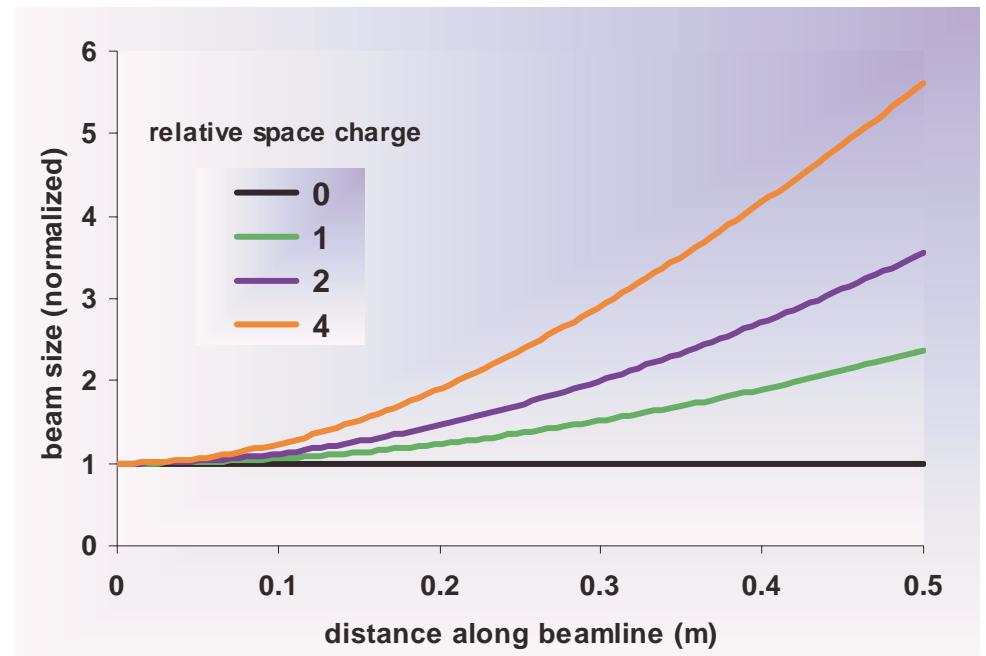
Perveance (K) is an important beam transport parameter that determines space charge forces

$$K \propto \frac{I \sqrt{m}}{E^{3/2}} \propto \frac{I}{mv^3}$$

Methods for controlling space charge for low energy transport – Magnetic confinement, beamline plasma's, PEF's, etc.

Example of beam expansion due to space charge:

2 keV B+ 10 mA





Space charge is significantly improved for Boranes

	B^+ (11)	BF_2^+ (49)	$B_{10}H_x^+$ (~ 120)	$B_{18}H_x^+$ (~ 210)
Dopant flux for equivalent ion current	1	1	10	18
Ion energy for equivalent dopant velocity	1	4.45	~ 11	~ 19
Relative space charge for equivalent dopant flux	1	0.22	~ 0.009	~ 0.0029

B18 delivers 18:1 dopant for given ion charge



Space charge is significantly improved for Borane's

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Ion energy 19 times higher



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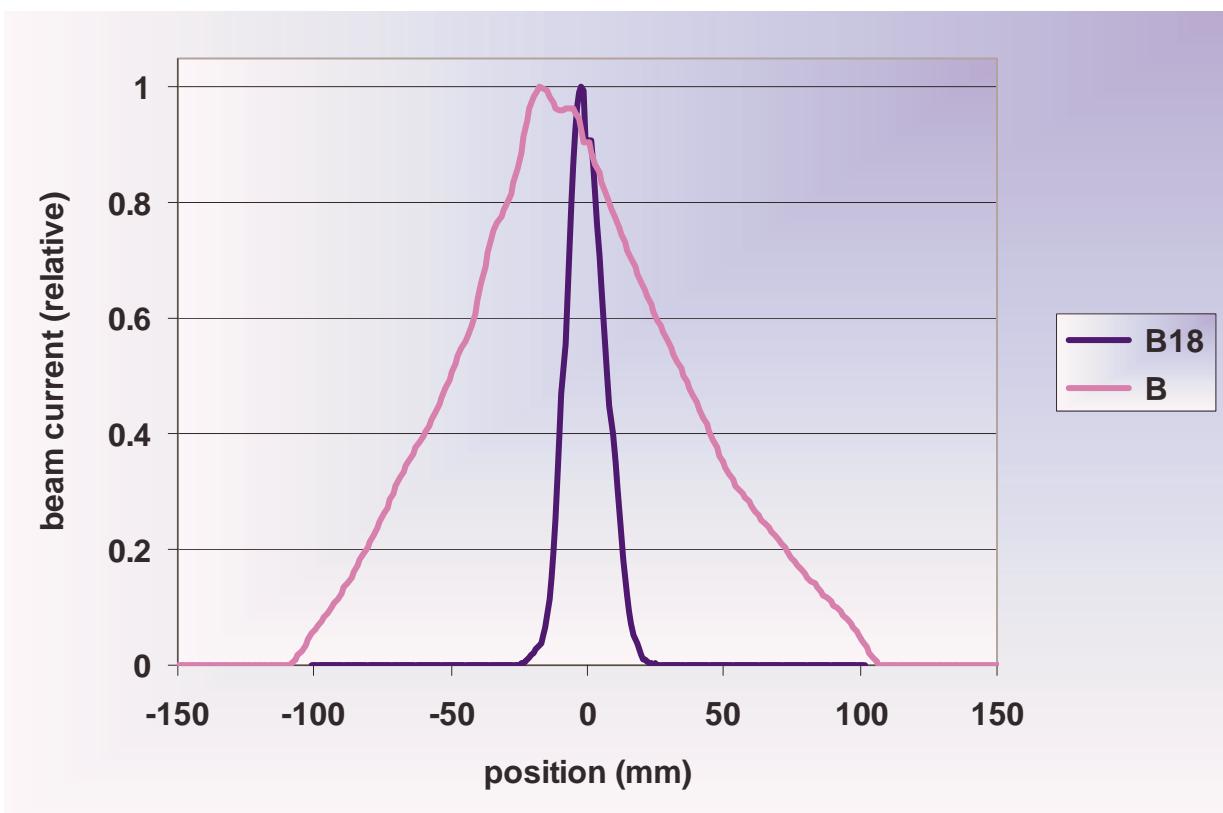
Space charge
reduced by a factor
of more than 300



Reduced space charge with borane molecules results in beam size improvement – experimental evidence

Lower space charge can result in a much narrower beam profile at the wafer

Results in increased beam utilization efficiency on multi-wafer and scanned platforms

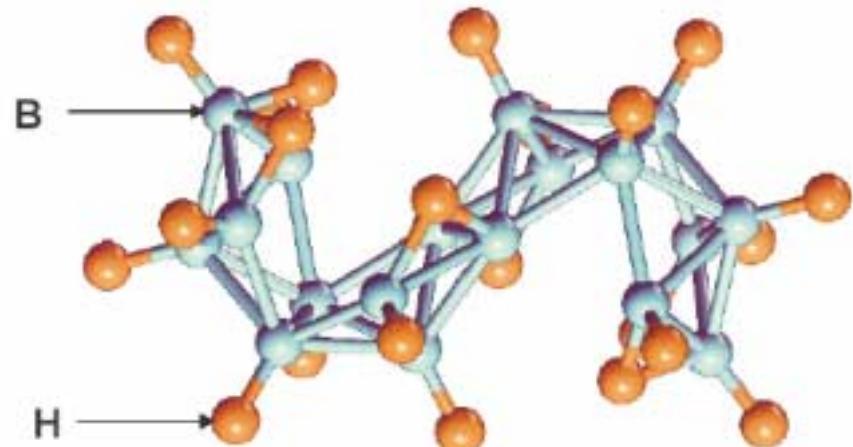


Axcelis 8250



Cluster Implant Productivity *Outline*

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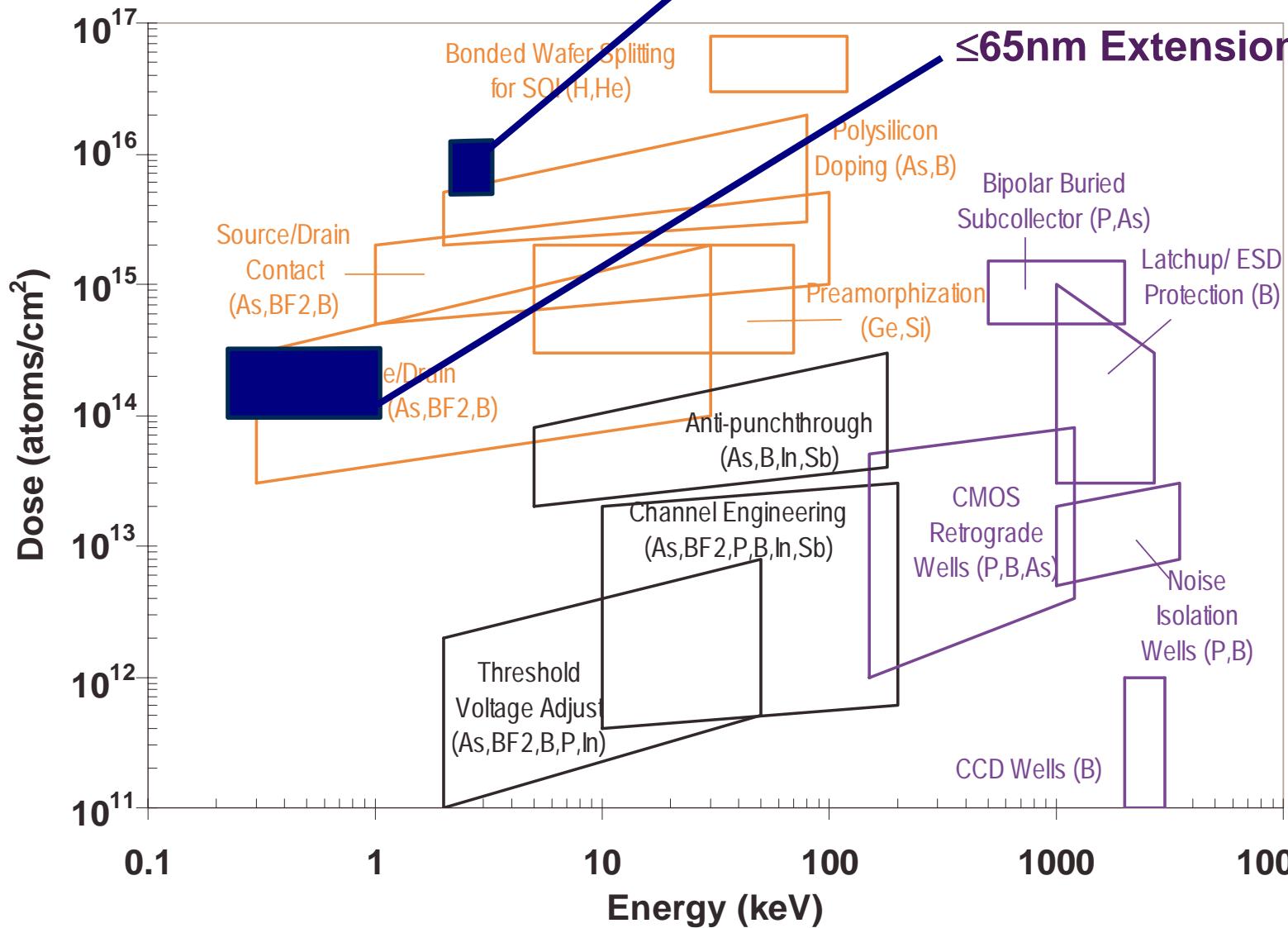




Potential B10 and B18 Applications

$\leq 90\text{nm}$ Dual Poly Gate Doping

$\leq 65\text{nm}$ Extension





Ultra Low Energy Extension Device Investigations

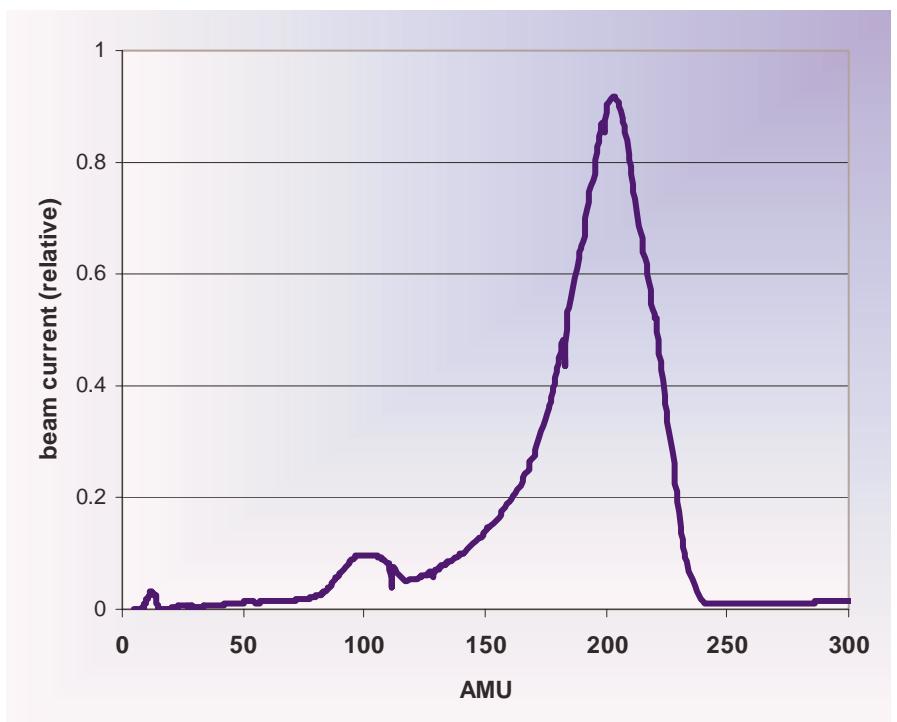
- Published
 - 2004 Renesas/SemEquip @ IIT (B_{18}^+ ; showed B^+ equivalence)
 - 2002 Agere/Axcelis (B_{10}^+ ; showed B^+ equivalence)
 - 1997 Fujitsu (B_{10}^+ ; showed B^+ equivalence)
- All indications that big borane will work for extension implants



B₁₈H₂₂ Spectrum

- Typical mass spectrum
 - With mass resolution ~ 15
- Peak B₁₈ current in the range of AMU 200 – 210
 - Contains contributions ranging from ¹⁰B₁₈H₆ to ¹¹B₁₈H₂₂
 - Contribution from any B₁₇ or other B_x combinations is typically very small

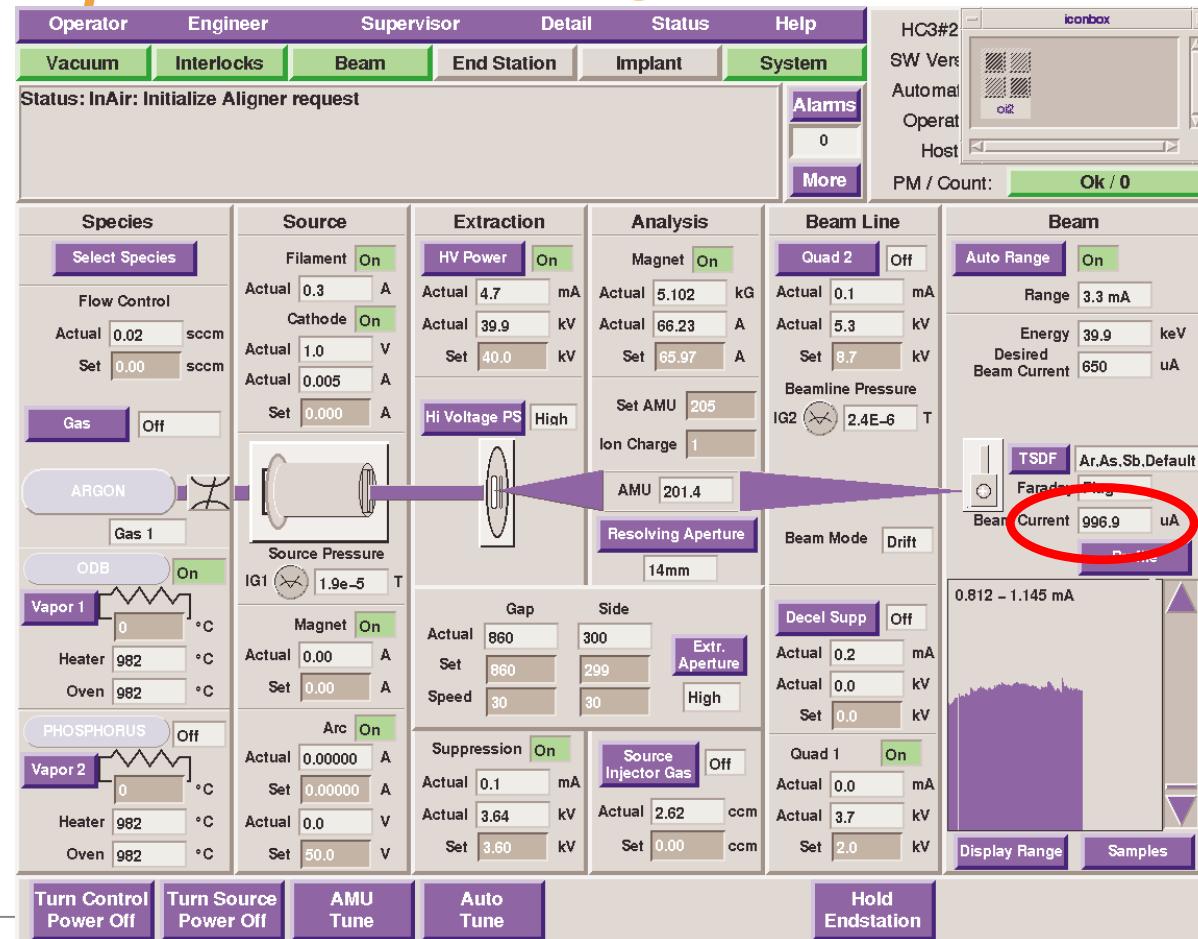
2 keV B equivalent spectrum





SemEquip Clusterlon™ Source

18 mA equivalent current @ 2 keV on Axcelis Ultra



996.9 μ A

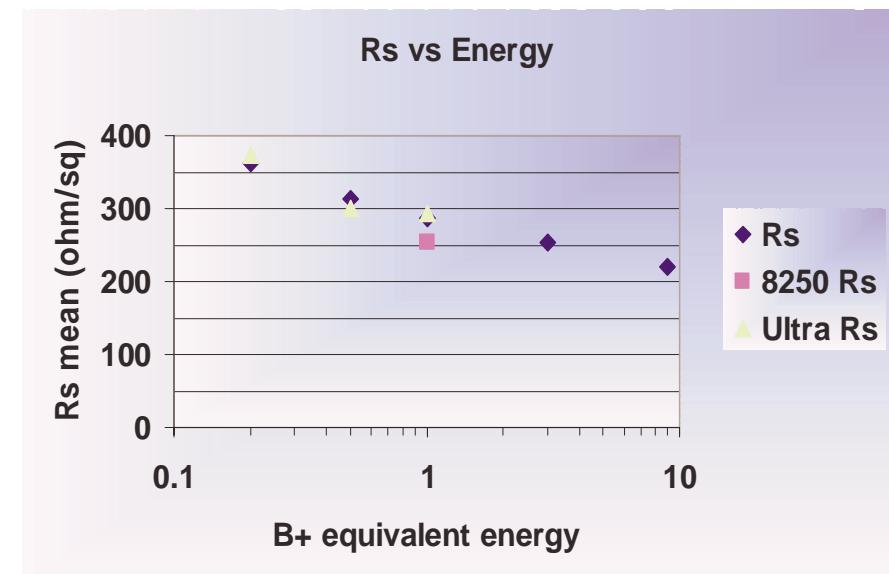


Courtesy Dr. Ned Eisner Nov-2004

ClusterIon™ Source Evaluation on Axcelis 8250 – Uniformity & Dose

- B18 bare wafer uniformity roughly equivalent to B+ results
 - No SEF was used
 - All beams corrected to better than 0.5% non-uniformity
- Dose matching to Ultra confirmed

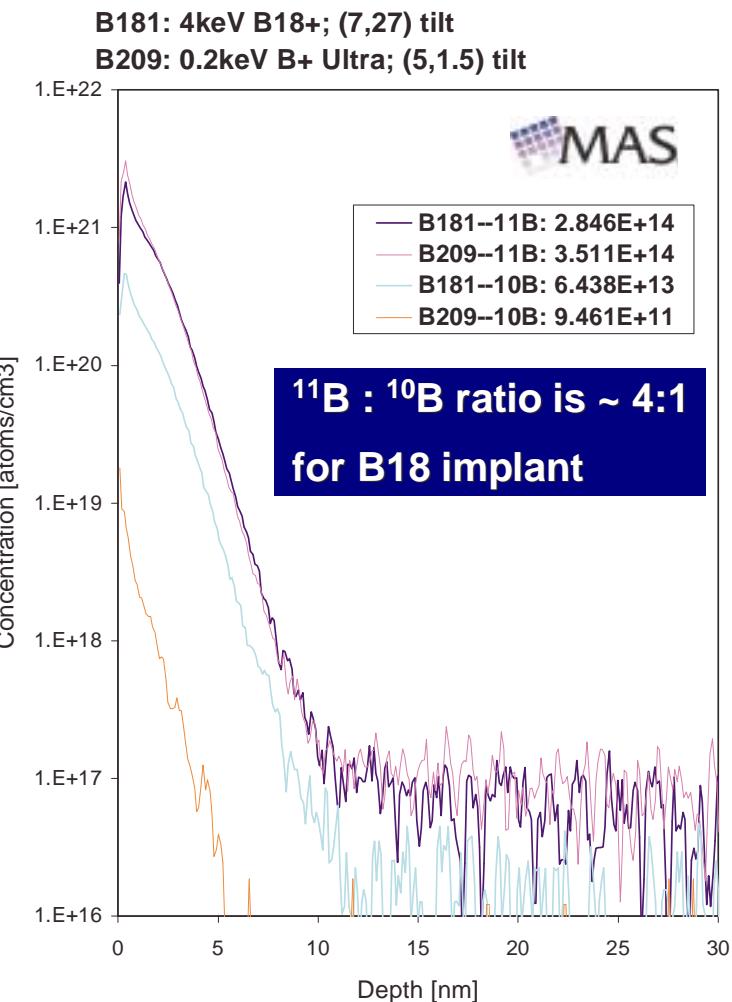
Energy (equiv keV)	Ibeam (equiv uA)	Rs uniformity (1 sigma)
9	1178	0.54
3	1190	0.71
1	1176	0.99
0.5	1041	1.07
0.2	536	1.98





0.2 keV Equivalent Boron SIMS – Comparison with Ultra

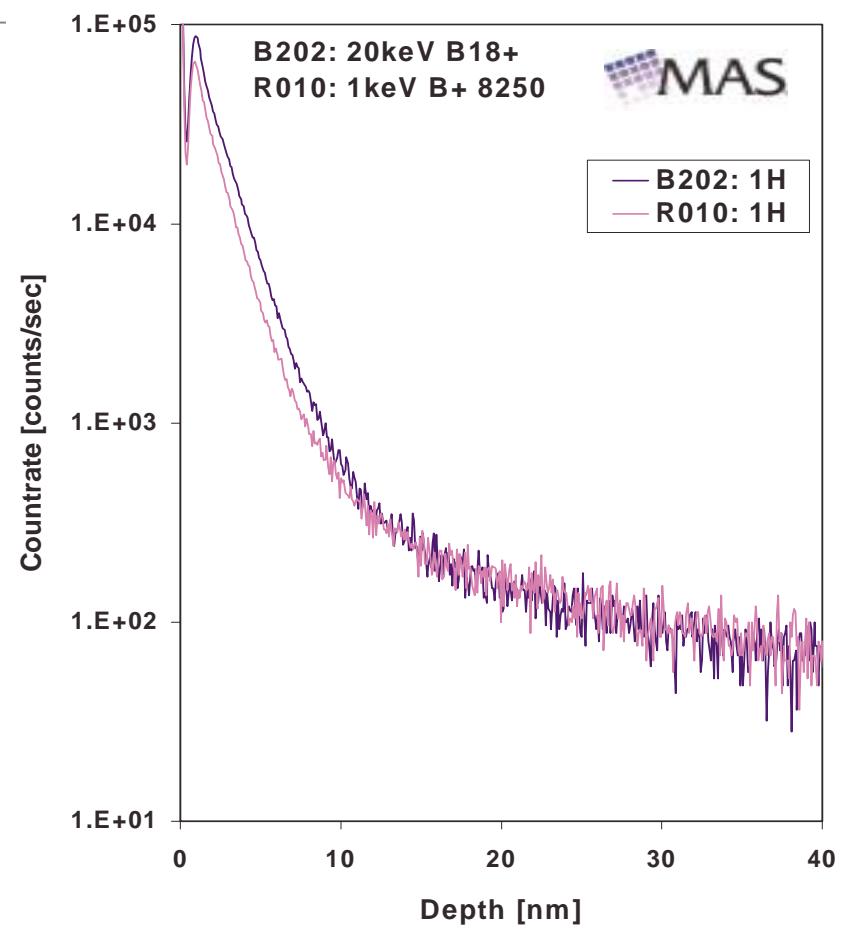
- Overall SIMS profile is well-matched to B⁺ implant
- Large difference in ¹⁰B concentrations is expected
 - Ultra uses enriched BF₃
 - B₁₈ is isotopically natural (contains ¹⁰B and ¹¹B)





Hydrogen SIMS

- H SIMS profile with B_{18} shows small difference from standard B^+ implant
 - Assumption: implanted hydrogen relatively small compared to hydrogen at the wafer

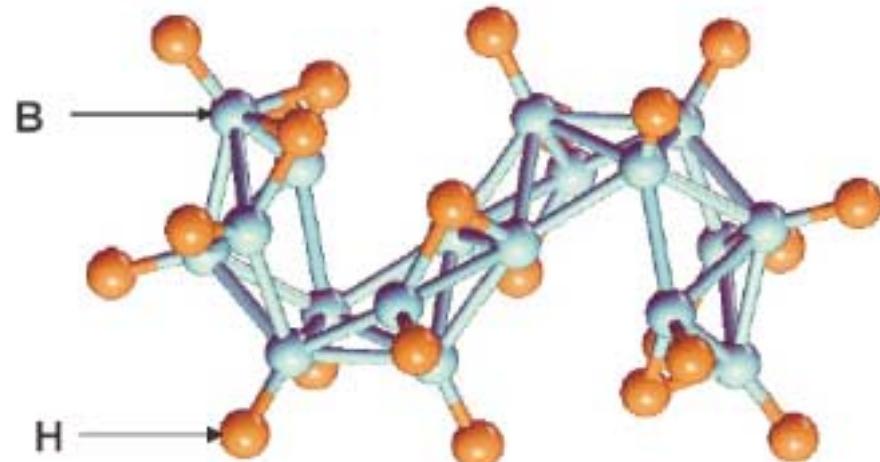




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Summary

- **Significant productivity improvements are possible with Borane implantations**
 - Extension Implants
 - Dual Poly Gate
- **Existing machines support generation and transport**
 - But have limits in the maximum energy due to the analyzer magnet capability
 - Dedicated machines?
- **Process integration is promising**
 - Little measureable difference between borane implants and boron implants.